

INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

To Commissioner For Patents

Enclosed herewith is a Form PTO-1449, required copies of documents listed thereon, and a concise explanation of their relevance is described below or enclosed herewith per 37 CFR 1.97.

Application Number

Filing Date

CONCURRENTLY

First Named Inventor

Rene Monshouwer
et al

Group Art Unit

Examiner Name

Attorney Docket Number

NI 000771

U.S. PTO
09/040818

#4
180201
R. Talb

These documents may be relevant in that they have been:

- ☒ considered in drafting the specification of the above-referenced application;
- ☒ cited in the specification of the above-referenced application;
- ☐ previously submitted or cited in U.S. patent application(s) _____ which are relied on for an earlier effective filing date under 35 U.S.C. 120 (no copy required); or
- ☐ cited as an "X" or "Y" document in a foreign Patent Office search report on a foreign counter part application, a copy of which report is also enclosed;
☐ I hereby certify that these documents were first cited in any communication with a foreign Patent Office for a counterpart foreign application not more than three (3) months ago;
- ☐ Otherwise a concise explanation of the relevance of each document is append hereto.
☐ I hereby certify that not one of these documents was cited in any communication with a foreign Patent Office nor was any known to any individual designated in §1.56(c) more than three (3) months ago.

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED

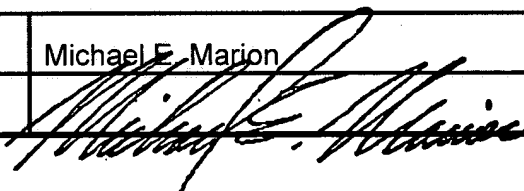
Name (Print Type)

Michael E. Marion

Registration No. (Attorney/Agent)

32,266

Signature



Date

August 28, 2001

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE (REV. 7-80) PATENT AND TRADEMARK OFFICE										DOCKET NO. N1 000771		Serial No.	
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)										Applicant Rene Monshouwer et al			
										Filing Date Concurrently		Group	

U.S. PATENT DOCUMENTS													
Ex. Int.	Document Number	Date	Name	Class	Sub-class	Filing Date If Approp.							
	AA 4 7 3 7 8 2 3	4/12/88	Bouwer et al	355	53	10/14/86							
	AB 5 0 2 6 1 6 6	6/25/91	Van der Werf	356	401	10/1/84							
	AC 5 1 9 1 2 0 0	3/2/93	Van der Werf	250	201	12/16/91							
	AD 4 3 5 6 3 9 2	10/26/82	Wittekoek et al	250	201	6/11/80							
	AE 4 8 6 1 1 6 2	8/29/89	Ina et al	356	401	11/15/88							
	AF 5 4 1 4 5 1 4	5/9/95	Smith et al	356	363	6/1/93							
	AG 4 7 7 8 2 7 5	10/18/88	Van den Brink	356	401	9/24/86							
	AH 4 2 5 1 1 6 0	2/17/81	Bouwhuis et al	356	401	7/13/78							
	AI 5 2 4 3 1 9 5	9/7/93	Nishi	250	548	12/29/92							

FOREIGN PATENT DOCUMENTS													
Document Number	Date	Country	Class	Sub-Class	Trans.								
					Yes	No							
AJ 0 4 9 8 4 9 9 A 1	8/12/92	Europe			X								
AK 9 8 3 9 6 8 9 A 1	9/11/98	World			X								

OTHER (Including Author, Title, Date, Pertinent Pages, Etc.)	
AL	"Submicrometer Lithographic Alignment and Overlay Strategies", by Saleem H. Zaidi et al, SPIE Vol. 1343, 1990, pages 245-255.
AM	"Overlay Accuracy Measurement Technique using the Latent Image on a Chemically Amplified Resist", by K. Yamashita et al., J. Appl. Phys. Vol. 35, 1996, pages 56-60.
AN	"Submicron 1:1 Optical Lithography", by David A. Markle, Semiconductor International May 1986.
Examiner _____ Date Considered _____	